

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	53447	(conduct\$3 wir\$3) same mask same (expos\$3 remov\$3 etch\$3 pattern\$3)	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/29 18:56
L3	10735	L2 and ((IC die chip) same (connect\$3 fitt\$3))	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/29 18:56
L4	7294	L3 and (electrical\$3 near5 connect\$3)	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/29 18:57
L5	6425	L4 and (insulat\$3 dielectric)	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/29 17:49
L6	2859	L5 and resin	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/29 18:57
L11	28146	(conduct\$3 wir\$3) and mask and (expos\$3 remov\$3 etch\$3 pattern\$3)	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/29 18:56
L12	817	L11 and ((IC die chip) and (connect\$3 fitt\$3))	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/29 18:56
L13	277	L12 and (electrical\$3 and connect\$3)	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/29 18:57
L14	137	L13 and (insulat\$3 resin)	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/29 18:57